

Title (en)
TITANIUM MATERIAL

Title (de)
TITANMATERIAL

Title (fr)
MATÉRIAU DE TITANE

Publication
EP 2615186 A4 20171018 (EN)

Application
EP 10856960 A 20100908

Priority
JP 2010065369 W 20100908

Abstract (en)
[origin: EP2615186A1] An object of the present invention is to provide a titanium plate having high strength and excellent workability. In order to achieve this object, the present invention provides a titanium material having an iron content of 0.60% by mass or less and an oxygen content of 0.15% by mass or less, with the balance being titanium and unavoidable impurities, the titanium material having a worked structure formed by working accompanied by plastic deformation and a recrystallized structure formed by annealing after the working, wherein the titanium material is formed such that the average particle size of crystal grains of the recrystallized structure is 1 μm or more and 5 μm or less, and the area of a non-recrystallized part in the cross-sectional area of the titanium material is more than 0% and 30% or less.

IPC 8 full level
C22C 14/00 (2006.01); **C22F 1/00** (2006.01); **C22F 1/18** (2006.01)

CPC (source: EP KR US)
C22C 14/00 (2013.01 - EP KR US); **C22F 1/00** (2013.01 - KR); **C22F 1/18** (2013.01 - EP KR US); **C22F 1/183** (2013.01 - EP US)

Citation (search report)

- [X] WO 2009118964 A1 20091001 - SUMITOMO METAL IND [JP], et al & US 2011017369 A1 20110127 - SHIRAI YOSHIHISA [JP], et al
- [X] WO 2010093016 A1 20100819 - SUMITOMO METAL IND [JP], et al & EP 2397569 A1 20111221 - SUMITOMO METAL IND [JP]
- [X] JP 2009161816 A 20090723 - SUMITOMO METAL IND
- [X] WO 2008050828 A1 20080502 - SUMITOMO METAL IND [JP], et al
- See references of WO 2012032610A1

Cited by
EP2716778A4; EP3276017A4; EP3050984A4

Designated contracting state (EPC)
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO SE SI SK SM TR

DOCDB simple family (publication)
EP 2615186 A1 20130717; EP 2615186 A4 20171018; CN 103069027 A 20130424; KR 20130059399 A 20130605; RU 2013115113 A 20141020; RU 2544976 C2 20150320; US 2013164166 A1 20130627; WO 2012032610 A1 20120315

DOCDB simple family (application)
EP 10856960 A 20100908; CN 201080068787 A 20100908; JP 2010065369 W 20100908; KR 20137004532 A 20100908; RU 2013115113 A 20100908; US 201013820768 A 20100908